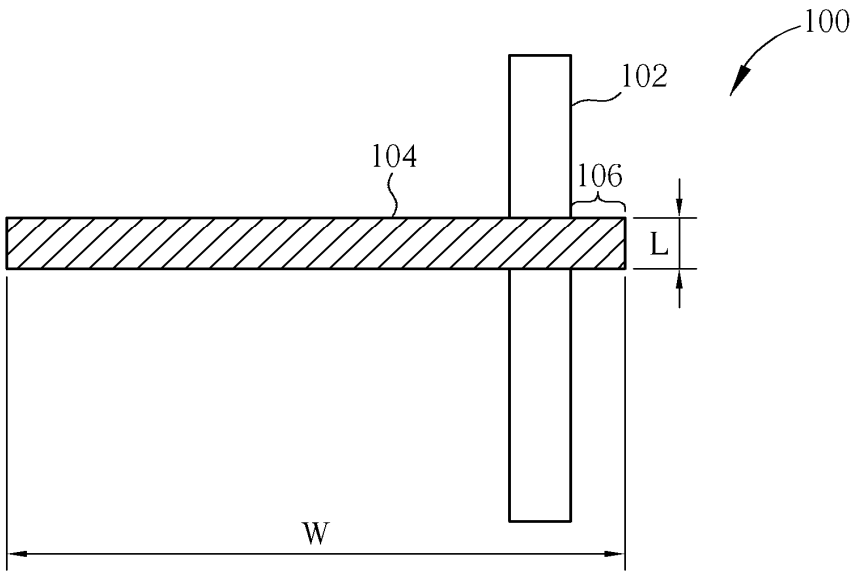


FIG. 1A PRIOR ART

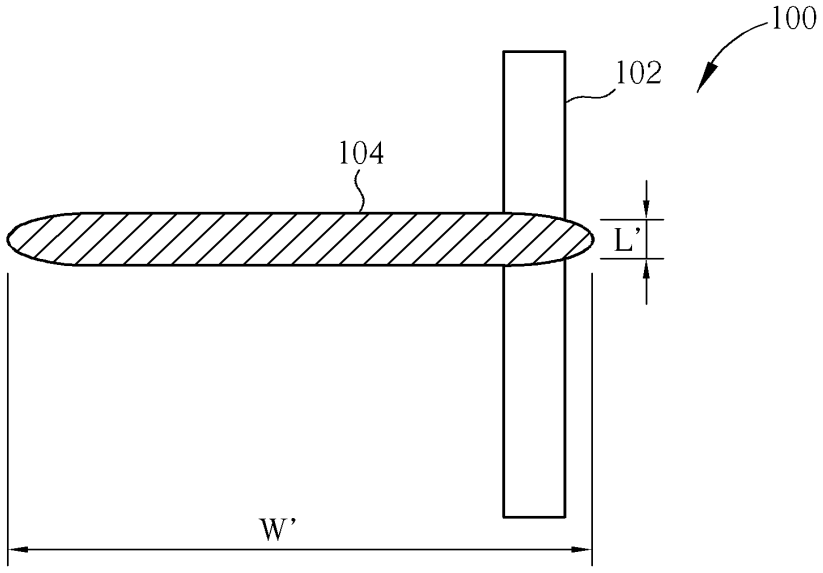


FIG. 1B PRIOR ART

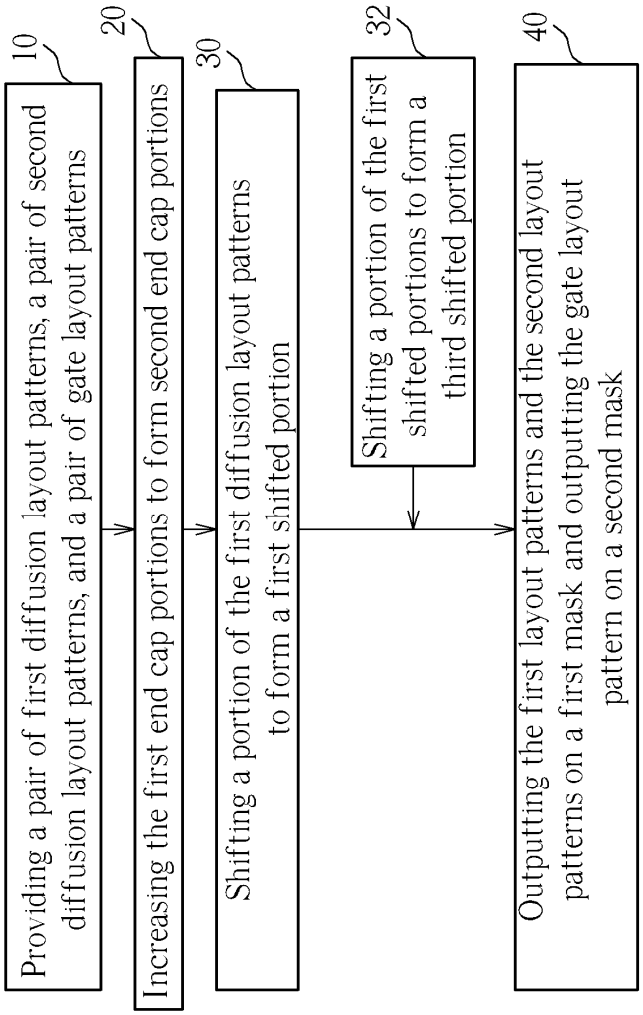

10
Providing a pair of first diffusion layout patterns, a pair of second diffusion layout patterns, and a pair of gate layout patterns
20
Increasing the first end cap portions to form second end cap portions
30
Shifting a portion of the first diffusion layout patterns to form a first shifted portion
32
Shifting a portion of the first shifted portions to form a third shifted portion
40
Outputting the first layout patterns and the second layout patterns on a first mask and outputting the gate layout pattern on a second mask

FIG. 2

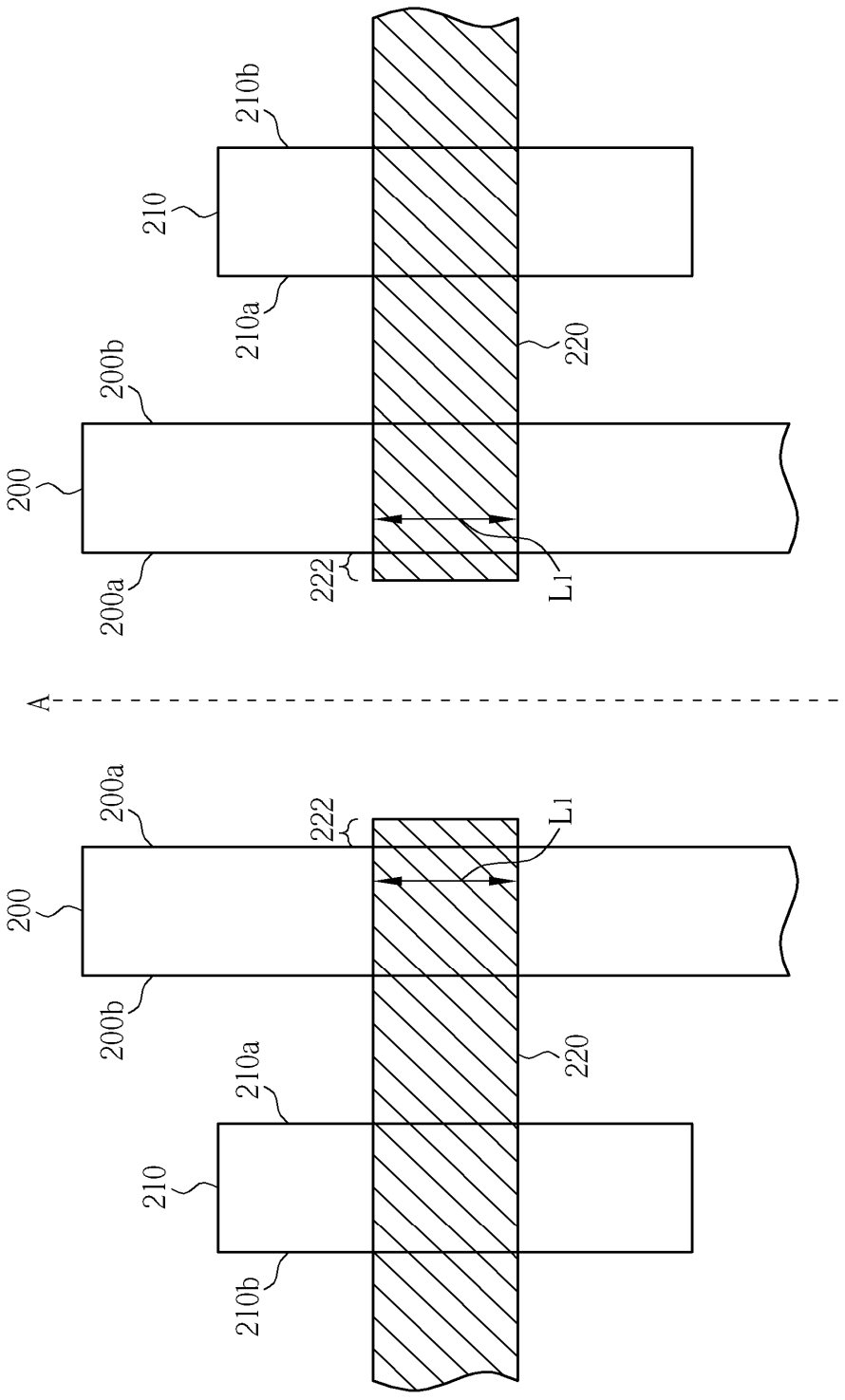


FIG. 3

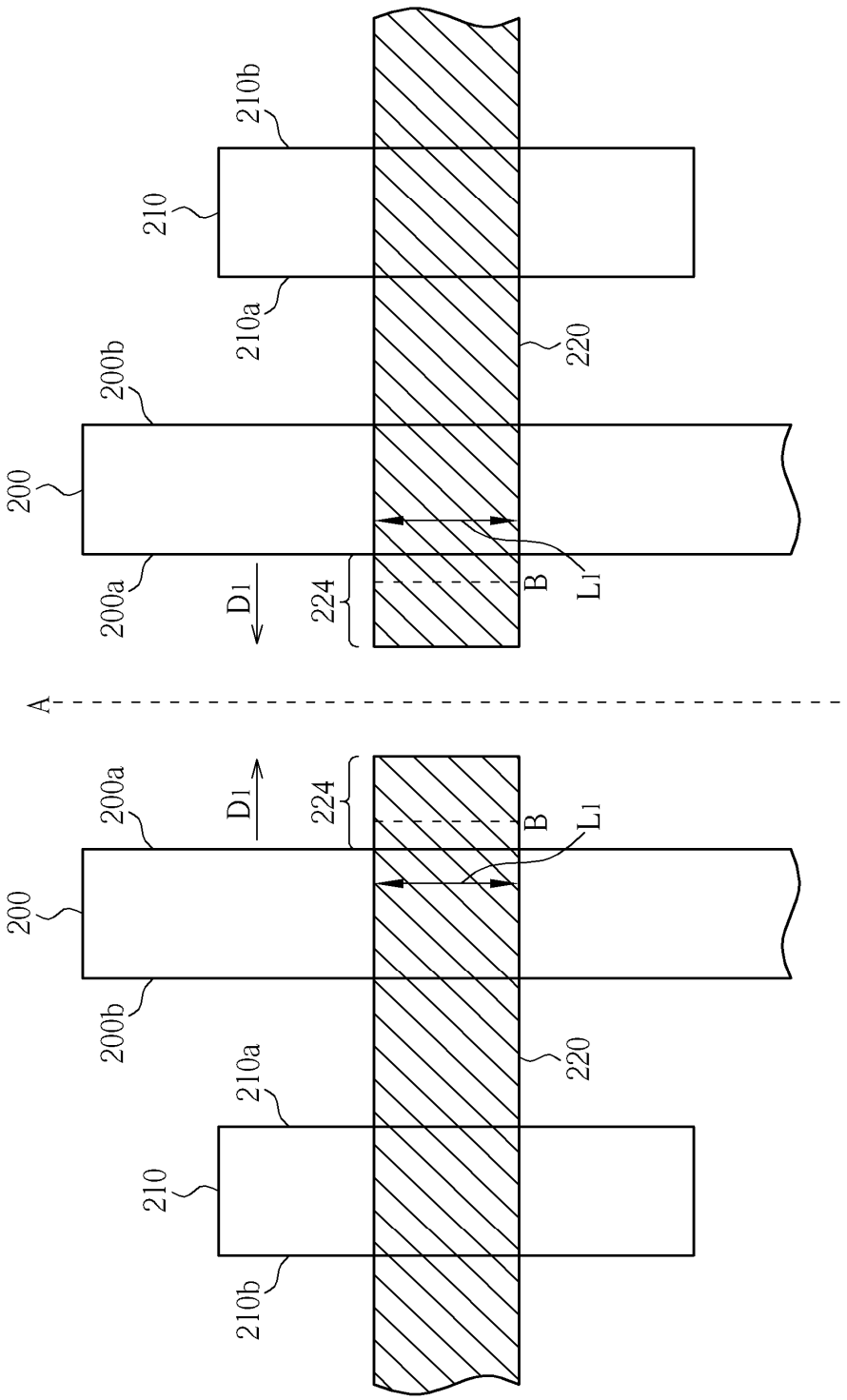


FIG. 4

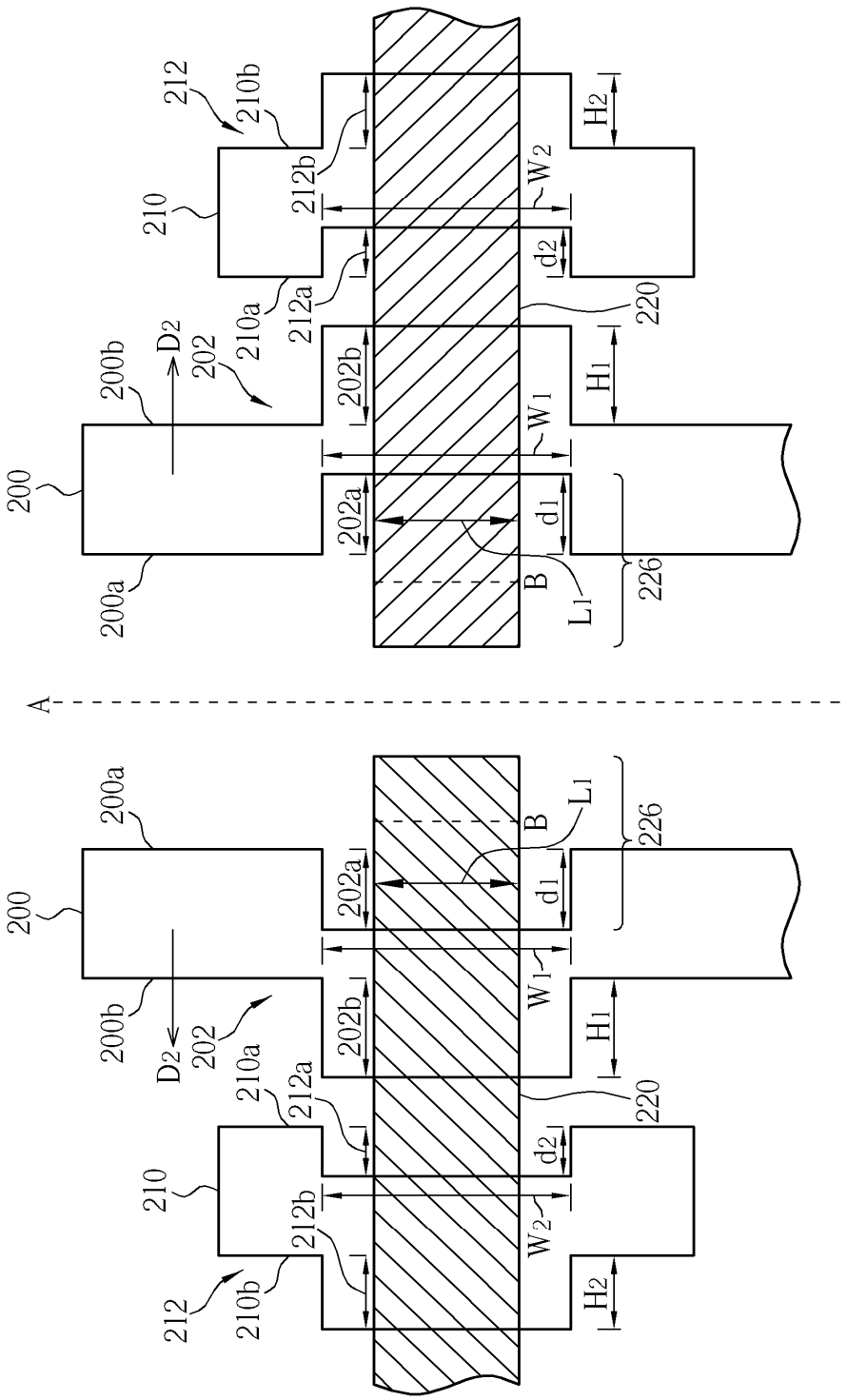

200
200a
200b
202
202a
202b
210
210a
210b
212
212a
212b
220
226
A
B
D2
W1
W2
H1
H2
d1
d2
L1

FIG. 5

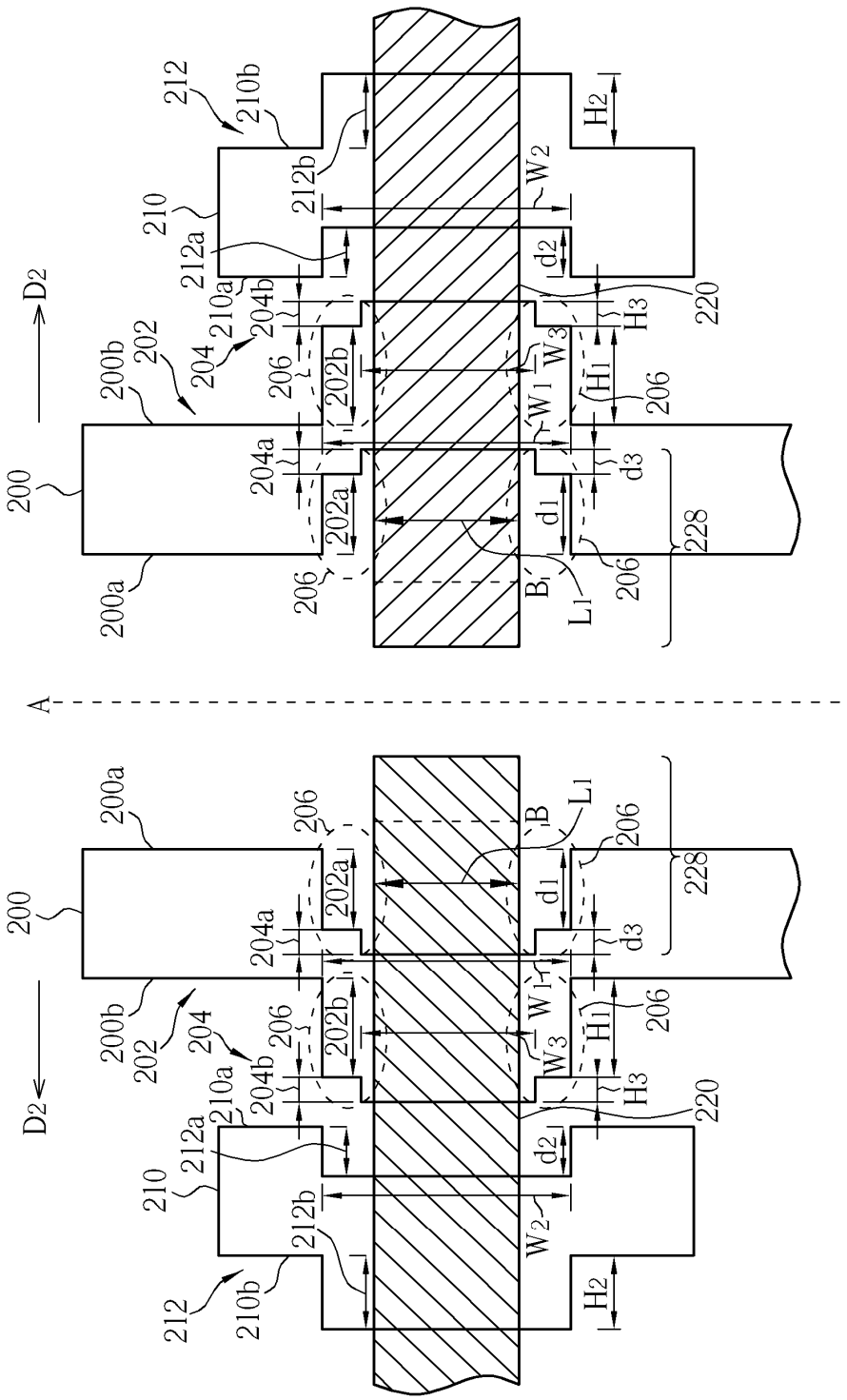

A
D2
D2
200
200a
200b
202
202a
202b
204
204a
204b
206
210
210a
210b
212
212a
212b
220
228
B
B'
L1
W1
W2
W3
H1
H2
H3
d1
d2
d3

FIG. 6

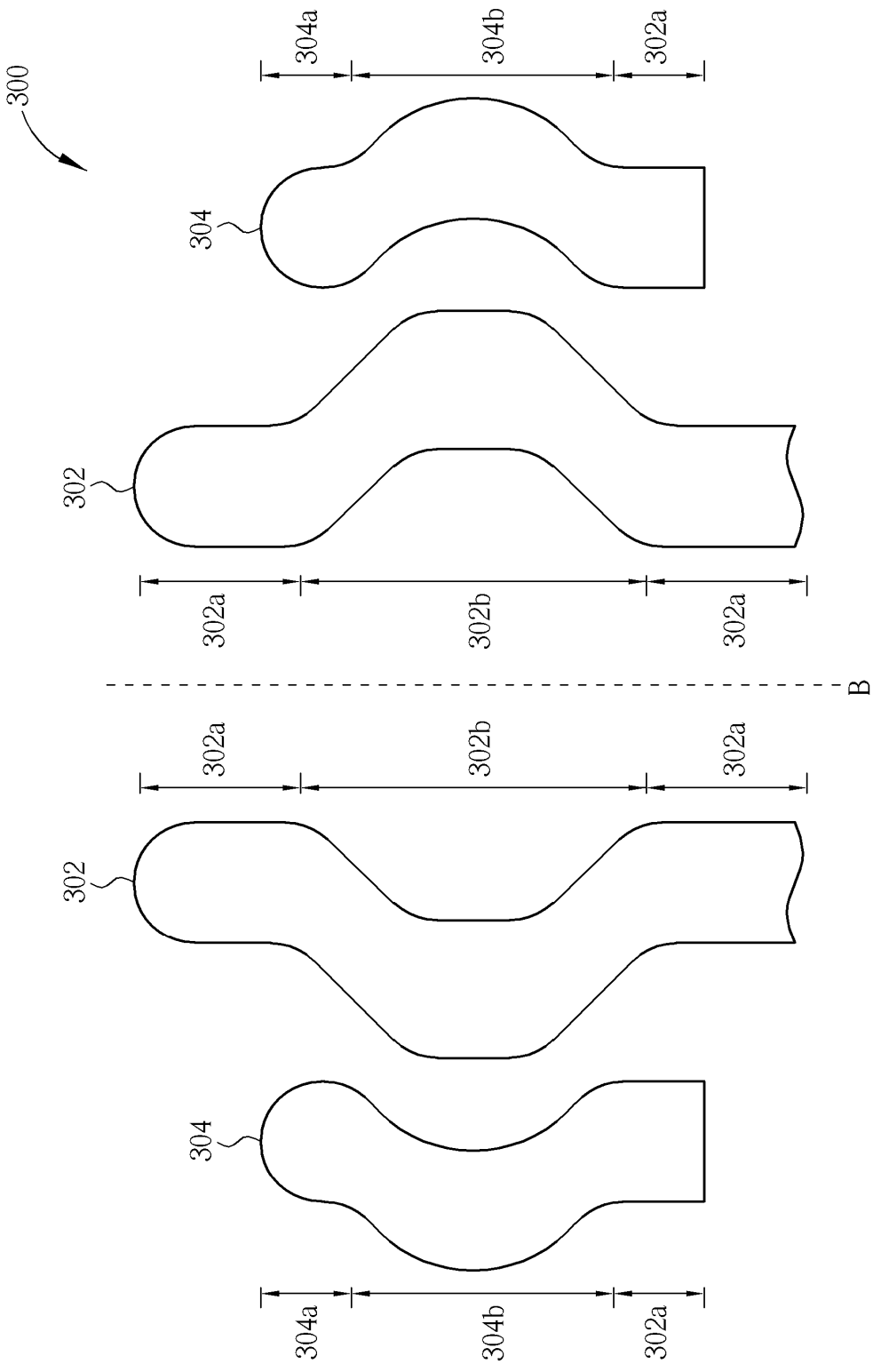

300
304
304a
304b
302a
302
302a
302b
302a
B
302a
302b
302a
302
304
304a
304b
302a

FIG. 7

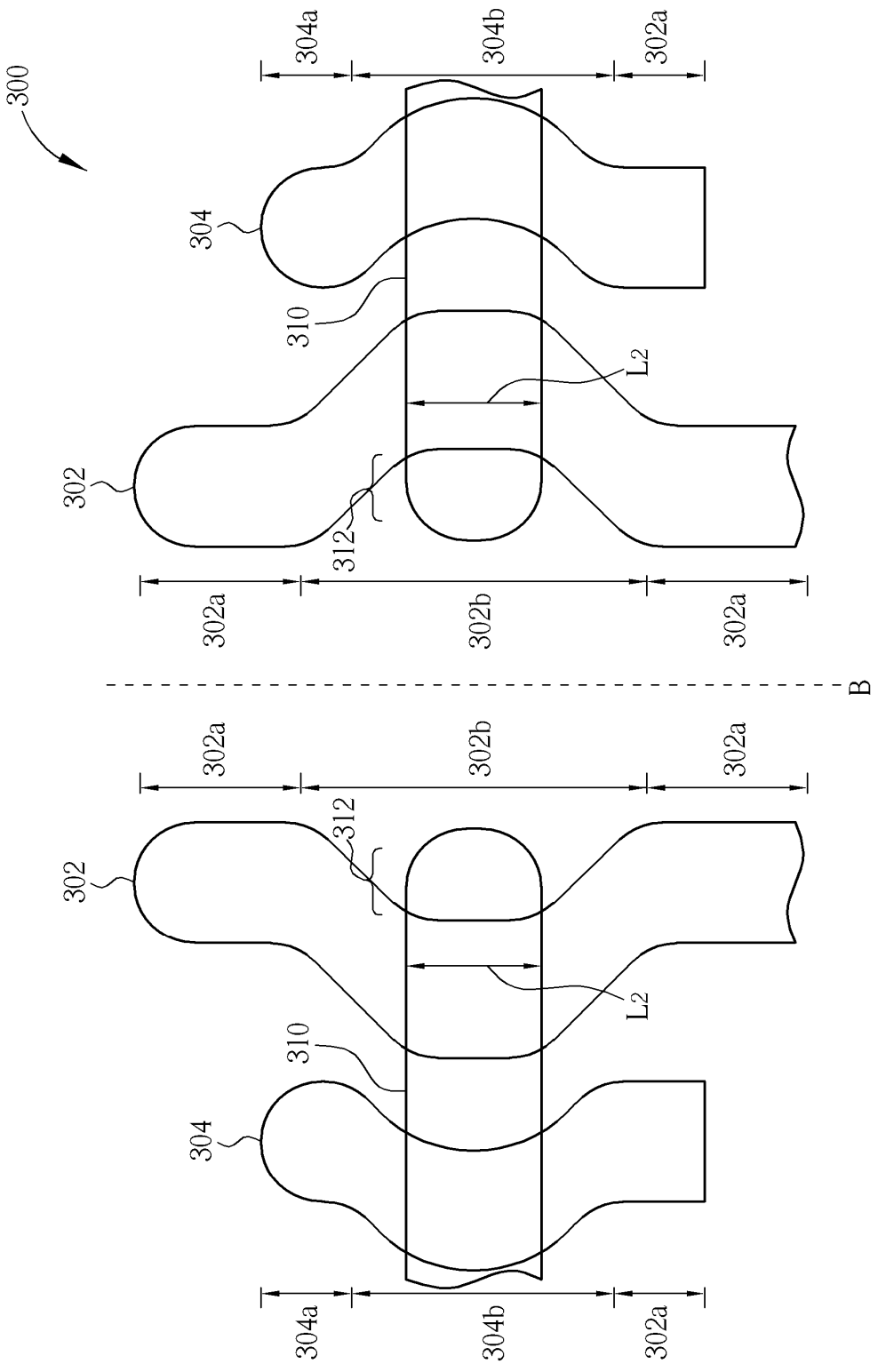

300
304a
304b
302a
304
310
L2
302
312
302a
302b
302a
B
302a
302b
302a
312
302
L2
310
304
304a
304b
302a

FIG. 8